

| L Number | Hits | Search Text | DB | Time stamp |
|-------------|------|--|---|---------------------|
| 1 | 213 | anneal\$5 near10 laser near10 ion near2 beam | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/27 10:58 |
| 2 | 11 | anneal\$5 near10 laser near10 ion near2 beam near5 (ar or argon) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/27 14:23 |
| 3 | 290 | (shin near2 hashimoto or takenobu near2 kishida or kyoko near2 egashira or yoshifumi near2 hata or toru near2 nishiwaki or tomoya near2 tanaka).in. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/27 14:25 |
| 4 | 3 | ((shin near2 hashimoto or takenobu near2 kishida or kyoko near2 egashira or yoshifumi near2 hata or toru near2 nishiwaki or tomoya near2 tanaka).in.) and (cobalt near2 (disilicide or silicide)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/27 14:43 |
| 5 | 4 | ("4861750" "4992298").pn. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/27 14:43 |
| - | 0 | neutron near4 beam near15 particle | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/02/04 11:05 |
| - | 421 | neutron near4 beam near15 particle | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/02/04 11:06 |
| - | 3 | neutron near4 beam near15 particle near10 (ar or argon) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/02/04 11:05 |
| - | 58 | neutron near4 beam near15 particle near10 ion | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/02/04 11:15 |
| - | 5 | neutron near4 beam near15 particle same lattice near2 defect | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/02/04 11:46 |
| - | 236 | (shin near2 hashimoto or takenobu near2 kishida or kyoko near2 egashira or toru near2 nishiwaki or tomoya near2 tanaka).in. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/02/04 11:47 |
| - | 15 | ((shin near2 hashimoto or takenobu near2 kishida or kyoko near2 egashira or toru near2 nishiwaki or tomoya near2 tanaka).in.) and silicide | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/02/04 11:49 |
| - | 2 | 4479829.pn. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/02/04 11:49 |

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| - | 1393 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:23 |
| - | 412 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) same (si or silicon) near3 (substrate or wafer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:23 |
| - | 116 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:36 |
| - | 2 | 4724223.pn. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:33 |
| - | 98 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) same (co or cobalt) near2 (film or layer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:36 |
| - | 73 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) same (co or cobalt) near (film or layer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:44 |
| - | 0 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) near5 insulat\$5 same (co or cobalt) near (film or layer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:44 |
| - | 0 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) near5 n\$1type same (co or cobalt) near (film or layer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:44 |
| - | 4 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) near5 dop\$5 same (co or cobalt) near (film or layer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:49 |
| - | 416 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (si or silicon) near3 (substrate or wafer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 16:50 |
| - | 16 | ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (si or silicon) near3 (substrate or wafer) near5 (insulat\$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 17:49 |
| - | 46 | epitax\$7 near10 ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (si or silicon) near3 (substrate or wafer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 17:49 |
| - | 19 | epitax\$7 near10 ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (si or silicon) near3 (substrate or wafer) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/25 18:04 |

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| - | 31 | epitax\$7 near10 ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) same (si or silicon) near3 (substrate or wafer) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/26 13:32 |
| - | 2 | "20020076882" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/26 10:25 |
| - | 4 | epitax\$7 near10 ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) same (si or silicon) near3 (substrate or wafer) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal) and mosfet | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/26 13:33 |
| - | 373 | (silicon near2 (oxide or dioxide) or (sio or "sio.sub.2")) same (argon or ar) near5 beam | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/26 14:47 |
| - | 3 | (silicon near2 (oxide or dioxide) or (sio or "sio.sub.2")) same (argon or ar) near5 beam same oxygen near5 atoms | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/26 14:47 |
| - | 52 | (silicon near2 (oxide or dioxide) or (sio or "sio.sub.2")) near10 (argon or ar) near5 beam | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/26 14:54 |
| - | 36 | (oxygen or "o.sub.2") near10 (implant\$5 or concentrat\$5) same (cobalt near2 (silicide or disilicide) or "cosi.sub.2") | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/26 14:55 |